10/081,439

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Kie Y. Ahn et al. Examiner:

iner: #X\_LU

Erial No.:

10/081,439

Group Art Unit: 2818

*\_* 

PATENT

Filed:

February 20, 2002

Docket: 1303.046US1

Title:

EVAPORATED LaAlO3 FILMS FOR GATE DIELECTRICS

## INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner for Patents Washington, D.C. 20231

In compliance with the duty imposed by 37 C.F.R. § 1.56, and in accordance with 37 C.F.R. §§ 1.97 et. seq., the enclosed materials are brought to the attention of the Examiner for consideration in connection with the above-identified patent application. Applicants respectfully request that this Information Disclosure Statement be entered and the documents listed on the attached Form 1449 be considered by the Examiner and made of record. Pursuant to the provisions of MPEP 609, Applicants request that a copy of the 1449 form, initialed as being considered by the Examiner, be returned to the Applicants with the next official communication.

Pursuant to 37 C.F.R. §1.97(b), it is believed that no fee or statement is required with the Information Disclosure Statement. However, if an Office Action on the merits has been mailed, the Commissioner is hereby authorized to charge the required fees to Account No. 19-0743 in order to have this Information Disclosure Statement considered.

The Examiner is invited to contact the Applicants' Representative at the below-listed telephone number if there are any questions regarding this communication.

Respectfully submitted,

KIE Y. AHN ET AL.

By their Representatives,

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.

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Date 10 SEPTEMBER 2002

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David R. Cochran

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September, 200

Name

Signature

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Substitute for form 1449A/PTO
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

THAT 8. THE AS many sheets as necessary)

<b>Application Number</b>	10/081439	
Filing Date February 20, 2002		
First Named Inventor Ahn, Kie		
Group Art Unit 2818		
Examiner Name	Unknown	

Sheet 1 of 1

Attorney Docket No: 01303.046US1

US PATENT DOCUMENTS						
Examiner Initial *	USP Document Number	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	Filing Date If Appropriate

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Foreign Document No	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	T <sup>2</sup>

	OTHER	R DOCUMENTS NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²
		GELLER, S., et al., "Crystallographic Studies of Perovskite-like Compounds. II. Rare Earth Aluminates", Acta Cryst. Vol. 9, (1956), pp. 1019-1025	
		GIESS, E.A., et al., "Lanthanide gallate perovskite-type substrates for epitaxial, high-T <sub>c</sub> superconducting Ba <sub>2</sub> YCu <sub>3</sub> O <sub>7-δ</sub> films", <u>IBM J. Res. Develop</u> . Vol. 34, No. 6, (November 6, 1990), pp. 916-926	
		LEE, A.E., et al., "Epitaxially grown sputtered LaAlO <sub>3</sub> films", <u>Appl. Phys. Lett.</u> 57 (19), (November 5, 1990), pp. 2019-2021	
		LEE, L.P., et al., "Monolithic 77 K dc SQUID magnetometer", Appl. Phys. Lett. 59 (23), (December 2, 1991), pp. 3051-3053	
		MOLODYK, A. A., et al., "Volatile Surfactant-Assisted MOCVD: Application to LaAlO <sub>3</sub> Thin Film Growth", <u>Chem. Vap. Deposition</u> Vol. 6, No. 3, (2000), pp. 133-138	
		PARK, BYUNG-EUN, et al., "Electrical properties of LaAlO <sub>3</sub> /Si and Sr <sub>0.8</sub> Bi <sub>2.2</sub> Ta <sub>2</sub> O <sub>9</sub> /LaAlO <sub>3</sub> /Si structures", <u>Applied Physics Letters</u> , Vol. 79, No. 6, (August 6, 2001), pp. 806-808	
		TAKEMOTO, J.H., et al., "Microstrip Resonators and Filters Using High-TC Superconducting Thin Films on LaAlO <sub>3</sub> ", <u>IEEE Transaction on Magnetics</u> , Vol. 27, No. 2, (March, 1991), pp. 2549-2552	
		WILK, G.D., et al., "High- $\kappa$ gate dielectrics: Current status and materials properties considerations", <u>J. Appl. Phys.</u> , Vol. 89, No. 10, (May 15, 2001), pp. 5243-5275	

**EXAMINER** 

**DATE CONSIDERED** 

10/081,439 PATENT

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Kie Y. Ahn et al.

Examiner:

Serial No.:

10/081,439

Group Art Unit: 2818

Filed:

February 20, 2002

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Title:

EVAPORATED LaAlO<sub>3</sub> FILMS FOR GATE DIELECTRICS

## **COMMUNICATION CONCERNING CO-PENDING APPLICATIONS**

Commissioner for Patents Washington, D.C. 20231

Applicant would like to bring to the Examiner's attention the following related copending applications in the above-identified patent application:

Serial No.	Filing Date	Attorney Docket	<u>Title</u>
09/779,959	02/09/2001	N/A	A METHOD AND APPARATUS FOR FABRICATION OF HIGHLY RELIABLE 1-nm TiO <sub>2</sub> GATE INSULATOR
09/838,335	04/20/2001	N/A	A METHOD FOR HIGHLY RELIABLE AMORPHOUS HIGH-K GATE OXIDE $HfO_2$
09/881,408	06/13/2001	N/A	HIGHLY RELIABLE STACKED AMORPHOUS GATE OXIDES (HfO <sub>2</sub> /La <sub>2</sub> O <sub>3</sub> )
09/908,767	07/18/2001	N/A	HIGH-INTEGRITY TiO₂ GATE INSULATOR, A METHOD AND APPARATUS FOR FABRICATION OF VERY UNIFORM THICKNESS ON 300mm WAFERS
09/944,981	8/30/2001	1303.021US1	CRYSTALLINE OR AMORPHOUS MEDIUM-K GATE OXIDES, Y <sub>2</sub> O <sub>3</sub> AND Gd <sub>2</sub> O <sub>3</sub>
09/945,535	08/30/2001	1303.026US1	HIGHLY RELIABLE AMORPHOUS HIGH-K GATE OXIDE, ZrO₂
10/027,315	12/20/2001	1303.033US1	LOW-TEMPERATURE GROWN HIGH-QUALITY ULTRA-THIN PRASEODYMIUM GATE DIELECTRICS

COMMUNICATION CONCERNING CO-PENDING APPLICATIONS

Serial Number: 10/081,439

Filing Date: February 20, 2002

**EVAPORATED LAAIO3 FILMS FOR GATE DIELECTRICS** 

Page 2 Dkt: 1303.046US1

10/028,643	12/20/2001	1303.030US1	LOW-TEMPERATURE GROWN HIGH QUALITY ULTRA-THIN CoTiO <sub>3</sub> GATE DIELECTRICS
10/052,983	01/17/2002	1303.031US1	HIGHLY RELIABLE AMORPHOUS HIGH-K GATE OXINITRIDE $Z_{rO_{x}N_{y}}$
10/099,194	03/13/2002	N/A	EVAPORATION OF Y-Si-O FILMS FOR MEDIUM-K DIELECTRICS

Respectfully submitted,

KIE Y. AHN ET AL.

By Applicant's Representatives,

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Signature



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Kie Y. Ahn et al.

Title:

**EVAPORATED LaAIO3 FILMS FOR GATE DIELECTRICS** 

Docket No.:

1303.046US1

Serial No.: 10/081,439

Filed:

February 20, 2002

Due Date: N/A

Examiner:

Group Art Unit: 2818

Commissioner for Patents Washington, D.C. 20231

We are transmitting herewith the following attached items (as indicated with an "X"):

A return postcard.

 $\frac{\overline{X}}{X}$ An Information Disclosure Statement (1 pg.), Form 1449 (1 pg.), and copies of 8 cited references.

Communication Concerning Co-Pending Applications (2 pgs.).

Please consider this a PETITION FOR EXTENSION OF TIME for sufficient number of months to enter these papers and please charge any additional required fees or credit overpayment to Deposit Account No. 19-0743.

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Reg. No. 46,632

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(GENERAL)